

Title (en)

AQUEOUS POLISHING COMPOSITION AND PROCESS FOR CHEMICALLY MECHANICALLY POLISHING SUBSTRATES CONTAINING SILICON OXIDE DIELECTRIC AND POLYSILICON FILMS

Title (de)

WÄSSRIGE POLIERZUSAMMENSETZUNG UND VERFAHREN ZUM CHEMISCH-MECHANISCHEN POLIEREN VON SUBSTRATEN MIT DIELEKTRISCHEN SILICIUMOXID- UND POLYSILICIUMFILMEN

Title (fr)

COMPOSITION DE POLISSAGE AQUEUSE ET PROCÉDÉ DE POLISSAGE MÉCANO-CHIMIQUE DE SUBSTRATS CONTENANT UN DIÉLECTRIQUE EN OXYDE DE SILICIUM ET DES FILMS EN POLYSILICIUM

Publication

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Application

EP 11846454 A 20111207

Priority

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- EP 10194476 A 20101210
- IB 2011055506 W 20111207
- EP 11846454 A 20111207

Abstract (en)

[origin: WO2012077063A1] An aqueous polishing composition comprising (A) abrasive ceria particles and (B) amphiphilic nonionic surfactants selected water-soluble and water-dispersible, linear and branched polyoxyalkylene blockcopolymers of the general formula I: $R[(B1)_m/(B2)_nY]_p(I)$, wherein the indices and the variables have the following meaning: m, n, and p integers = 1; R hydrogen atom or monovalent or polyvalent organic residue, except C5-C20 alkyl groups; (B1) block of oxyethylene monomer units; (B2) block of substituted oxyalkylene monomer units wherein the substituents are selected from two methyl groups, alkyl groups of more than two carbon atoms and cycloalkyl, aryl, alkyl-cycloalkyl, alkyl-aryl, cycloalkyl-aryl and alkyl-cycloalkyl-aryl groups; and Y hydrogen atom or monovalent organic residue, except C5-C20 alkyl groups; with the proviso that when (B) contains more than one block (B1) or (B2) two blocks of the same type are separated by a block of the other type.

IPC 8 full level

C09G 1/02 (2006.01); **C09K 3/14** (2006.01); **H01L 21/321** (2006.01)

CPC (source: EP KR US)

C09G 1/02 (2013.01 - EP KR US); **C09K 3/14** (2013.01 - KR); **C09K 3/1409** (2013.01 - EP US); **C09K 3/1463** (2013.01 - EP US); **H01L 21/30625** (2013.01 - US); **H01L 21/31053** (2013.01 - EP US); **H01L 21/32** (2013.01 - KR)

Citation (search report)

- [ID] US 2007077865 A1 20070405 - DYSARD JEFFREY M [US], et al
- [AD] JP 2001240850 A 20010904 - SANYO CHEMICAL IND LTD
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Designated contracting state (EPC)

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